Electronic Supplementary Material (ESI) for Physical Chemistry Chemical Physics.

Supplementary Materials

Adsorption kinetics of NO_2 gas on oxyfluorinated graphene film

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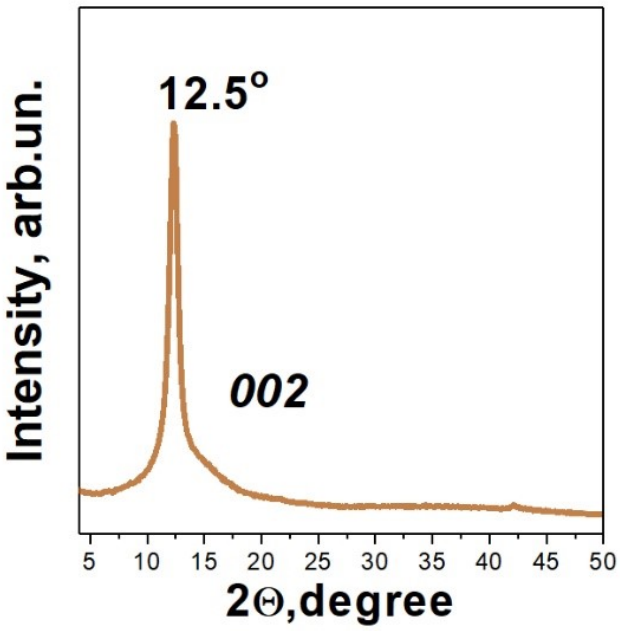

Figure S1. XRD pattern of oxyfluorinated graphite.

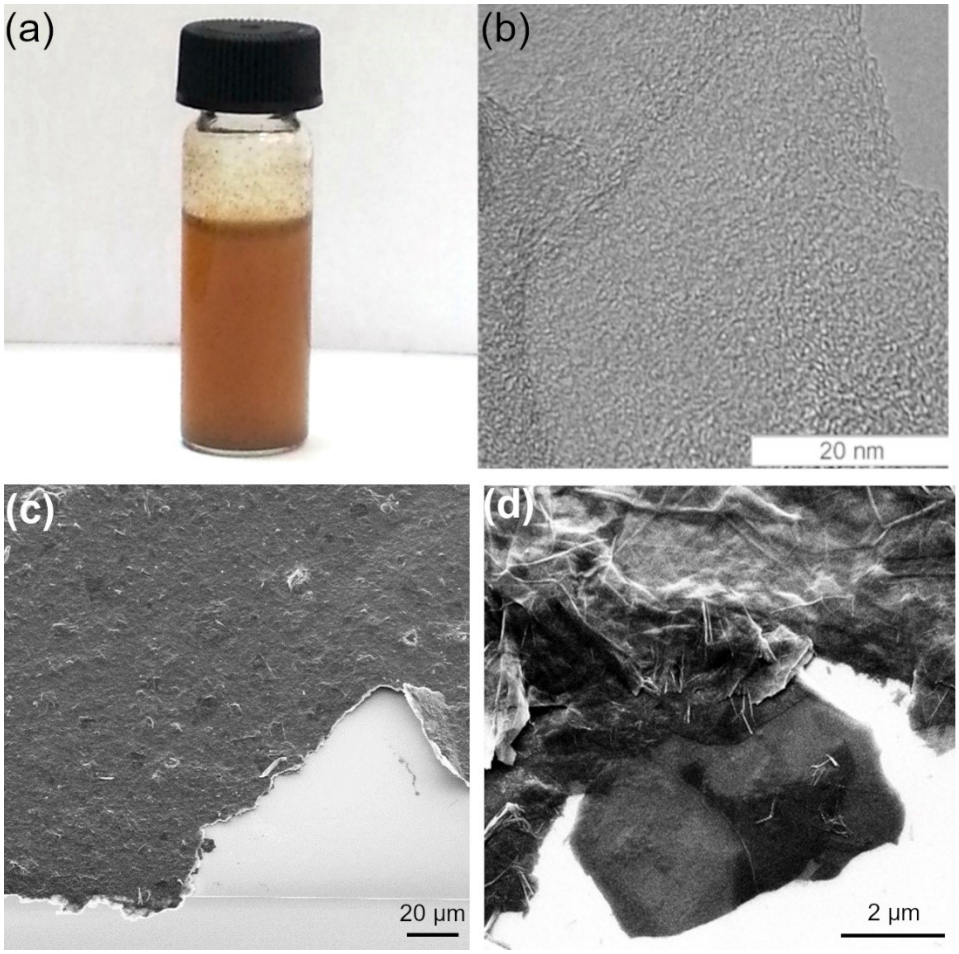

Figure S2. (a) OFG suspension in toluene, (b) high-resolution TEM image of OFG flake, (c,d) SEM images of OFG film deposited on SiO_2/Si substrate.

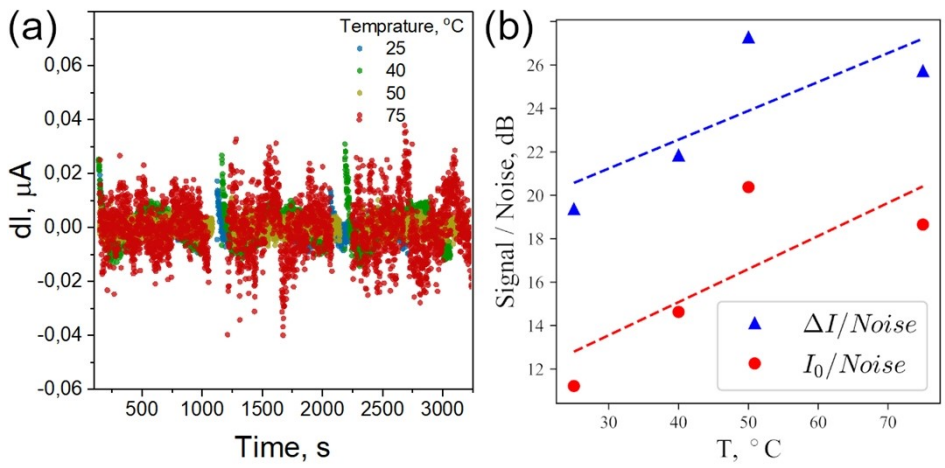

Figure S3. (a) Variation of noise level during NO_2 cycling at different temperature; (b) Signal-to-noise ratio vs operation temperature of OFG sensor.

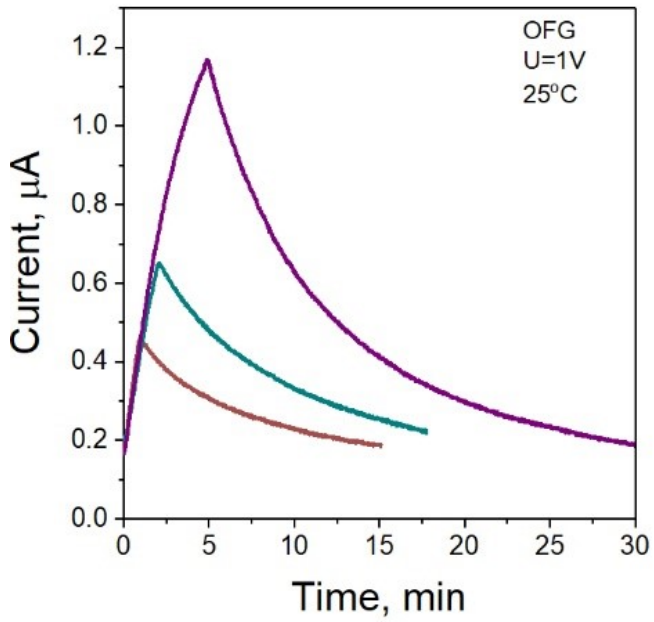

Figure S4. Responses of the OFG sensor to 100 ppm NO_2 at exposure times 60, 180 and 300 s.